





Implementation of a Comprehensive On-Line Closed-Loop Diagnostic System for Roll-to-Roll Amorphous Silicon Solar Cell Production

Introduction

- -- ECD and United Solar
- -- ECD/United Roll-to-Roll Production Technology
- -- Impact of NREL PV MaT/Man Funding

Summary of Phase I of the PV Man R&D 6 program

Task I: Implement Closed Loop Control of Film Thicknesses

Task II: Component Cell PVCD development – for use in future continuous online optimization

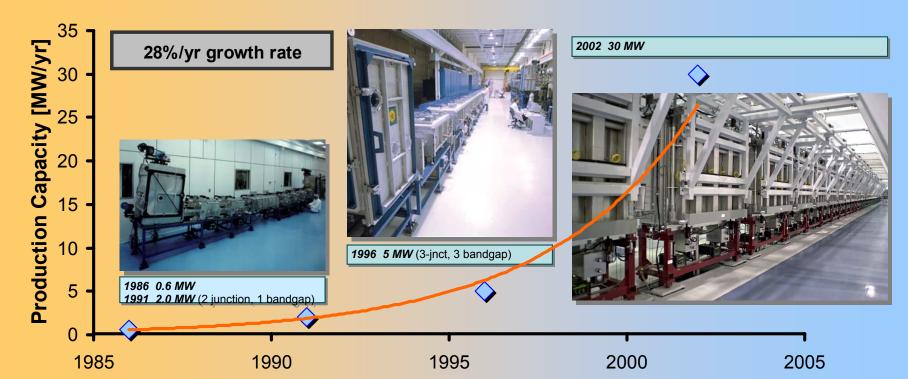
Task III: Plasma Diagnostics/Improved Deposition Technology

Task IV: Yield Improvements: Substrate Cleaning – prove efficacy of plasma cleaning and get rid of washing machine





-ECD/United Solar-



Year

ECD/United Solar Joint Venture manufacturing capacity over the last 15 years. During this time capacity has expanded at about 30%/year, with more rapid expansion in the last 5 years.

To see a World in a Grain of Sand And a Heaven in a Wild Flower Hold Infinity in the palm of your hand And Eternity in an hour

William Blake, Augeries of Innocence

Tim Ellison, Ph.D. Energy Conversion Devices, Inc.



FOR/United Color

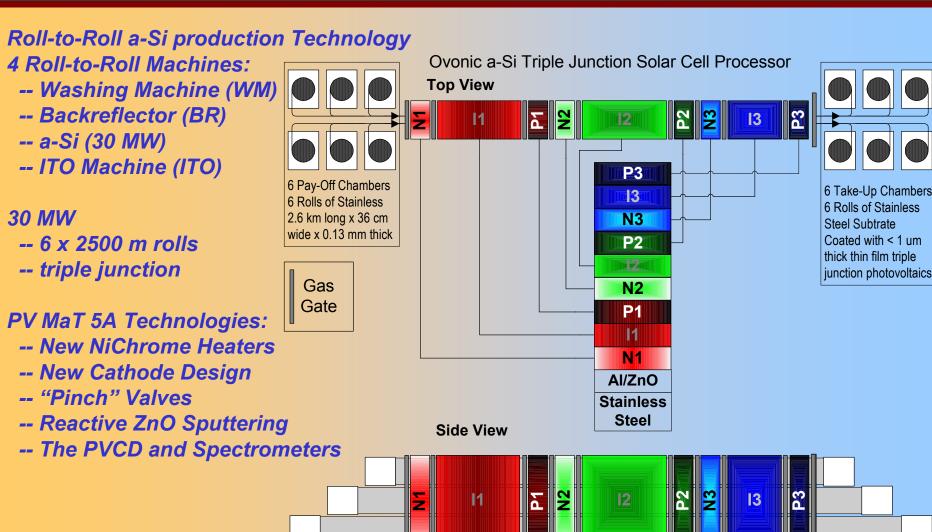


-ECD/United Solar-









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-United Solar BIPV Products-



First metal roofing PV Installation [NAHB RC 21st Century Townhouse Project in Maryland]. DOE PV:BONUS Program.



Architecturally- and aesthetically-integrated *Uni-Solar* shingle (left) and metal-roofing BIPV installations made from lightweight, flexible, rugged a-Si thin film PV.







Pre-PVMaT 5 – Windows in the Take-Up (TU) Chambers



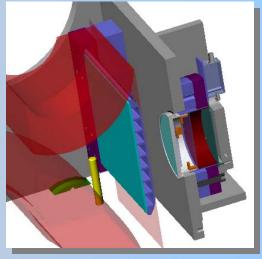
Post-PVMaT 5 – 1 PVCD and 1 Spectrometer in 5 MW TU Chamber -- Limited QA; Some QC and Diagnostics

Development of New "Eyes"

Can "see":

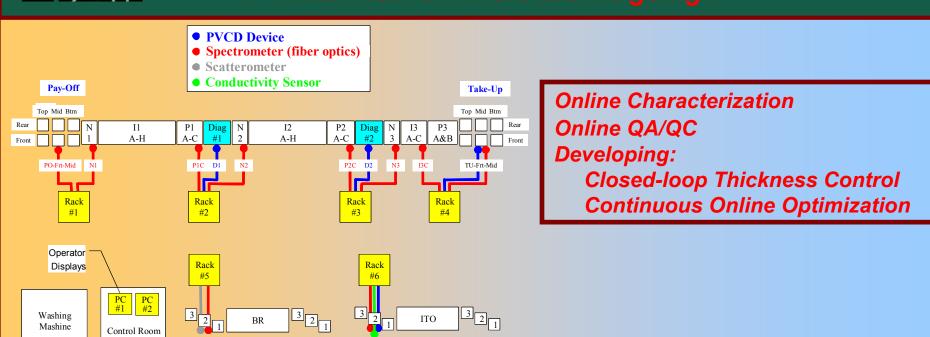
- -- Thickness
- -- V_{oc}
- -- J_{SC}/C, ...











Pay-Off

≈ 10 Networked Computer DAQ Systems 10's of Diagnostic Systems

Take-Up

Pay-Off

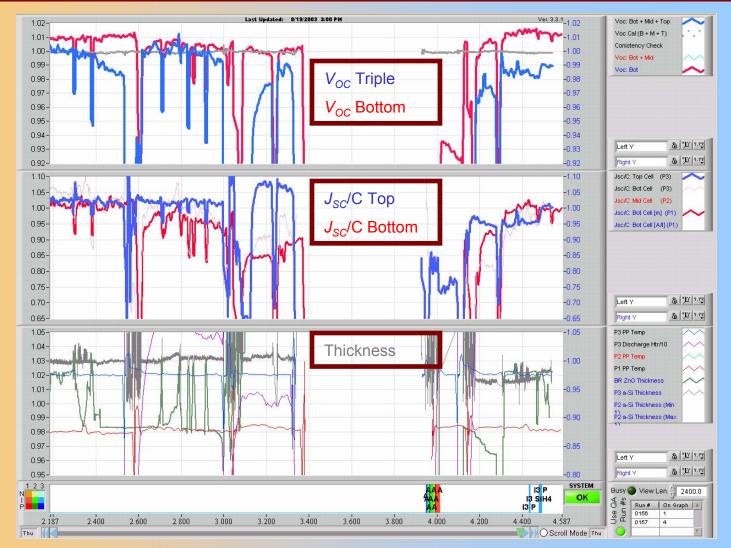
Take-Up

Roll-to-Roll Processor	Diagnostic Systems	Number	Measurement
Washing Machine	Optically Stimulated Electron Emission (OSEE)	2	Cleanliness
Backreflector	Scatterometer	1	Specular and diffuse reflection
	Reflection Spectrometers	1	ZnO film thickness
30 MW a-Si	Reflection Spectrometers	8	Thickness of BR and each n-, i-, and p-layer
	PVCD	4	Component and device electrical properties
ITO	Film conductivity	1	ITO conductivity
	Reflection Spectrometers	5	ITO film thickness
	PVCD	1	Device electrical properties; degree of shunts prior to passivation.





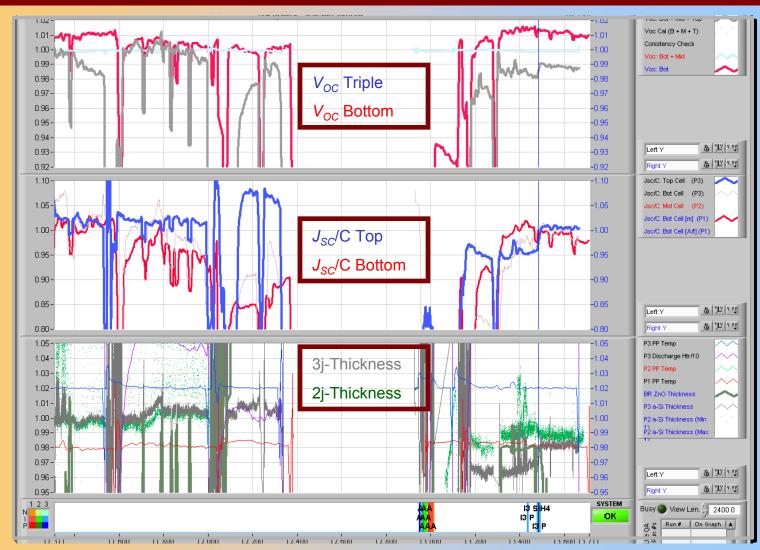
Success – What this Program is Yielding







Success – What this Program is Yielding









Questions -

The 30 MW has hundreds, if not thousands, of significant knobs. With 1-week turn-around of an experiment, how long would it take to completely optimize this machine?

How long to then optimize the 30 MW with the BR and ITO?

Think about this:

The R&D reactors can produce 1 – 3 samples/day, with poor statistics

With a complete online diagnostics systems we can perform hundreds of experiments/day 24/7 - with good statistics and no question about applicability to production.

How does one "automate" the experiment and experiment analysis process?

Can you symbiotically perform research on a production machine?

Production: Never change anything

Goal: make the exact same thing everyday

R&D: Constant experimentation; change everything

Goal: all material above average

YES -- while we admit that the primary purpose of the machines may be production, we are demonstrating that simultaneous R&D can benefit production.

We have developed a very good working relationship with the production personnel -- this is the most significant breakthrough in production technology in the last 10 years.







Work Areas:

Closed Loop Thickness Control in the ITO, BR, and a-Si Machines

Thickness measurement of all 9 layers in the triple junction a-Si device.

Phase I: Instrument BR, ITO, and a-Si TU; Second Generation a-Si Spectrometer Design ITO and BR Closed Loop Thickness Control System

Component Cell PVCD Development

V_{oc}, J_{sc}/C and other measurements of <u>each cell</u> in the triple junction device Implement Program of Continuous Online Optimization

Phase I: Design, Fabricate, Install, Retrofit 1st Component Cell PVCD

3. Plasma Diagnostics; Improving Deposition Hardware

> Phase I: Install Diagnostics; Analyze Plasmas Study Particle Production in a-Si Machine

Yield Improvements – Substrate Cleaning

Implement Plasma Cleaning – Eliminate 1 of 4 Roll-to-Roll Production Machines

Phase I: Online Cleanliness Diagnostic in WM

Correlate cleaning parameters with yield

Test plasma cleaning; compare with wet chemical cleaning

Determine and address most significant sources of yield reduction







TASK 1: Develop Closed-Loop Control of Film Thickness

-- Jeff Karn (ECD), Rujiang Liu and Jon Call (United Solar), Dave Dodge (Focus Software)

Milestones

Complete M-1.0.1	Complete testing of 1st generation a-Si reflection spectrometer in production
	equipment.

Complete M-1.1.1	Complete conceptual design of 1st generation ITO and ZnO closed-loop
	thickness-control systems.

Complete M-1.2.1	Complete installation	of :	2nd	generation	a-Si	reflection	spectrometer	in
	production equipment.							

Complete M-1	.3.1	Complete	fabrication	of	1st	generation	closed-loop	thickness-control
systems for ITO and ZnO.								

Complete M-1.4.1 Complete the Phase I portion of the effort under Task 1.

Deliverables

Complete	D-1.0.1	Report summarizing the testing of the 1st generation a-Si reflection spectrometer in the production equipment.
Complete	D-1.2.1	Report summarizing closed-loop thickness-control systems fabricated for the ITO and ZnO film thickness
Complete	D-1.3.1	ECD/United Solar confidential datalog display from a complete production roll of material demonstrating a-Si spectrometer thickness measurements



Comprehensive On-Line Closed-Loop Diagnostic Systems



Task I: Closed Loop Thickness Control I

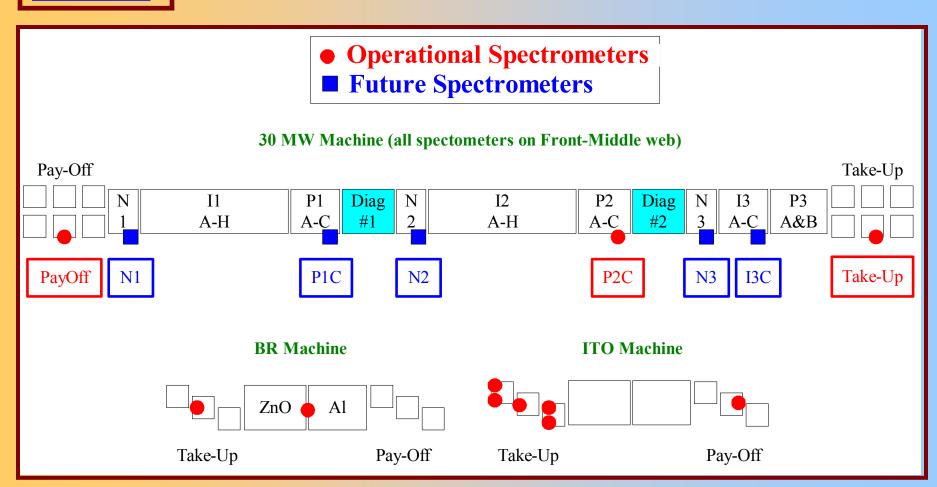
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Overview
First Generation a-Si Spectrometer
     Hardware
     Reflection Spectra
     Software
          Online DAQ
          Online Operator Inteface
          Offline Analysis Utilities
     Stop and Burn Technology (Unplanned Benefit)
          Trouble-shooting
          Integrals – motivation for 2<sup>nd</sup> Generation a-Si Spectrometer
Second Generation a-Si Spectrometer
     Design (actually, this is second design – Needed the "A" team)
     First Operation
Closed Loop Thickness Control System (BR)
     Spectra
     "Manual" Looping; Motivation (stabilize process by stabilizing input)
     System Design – looks straightforward ... (don't quote me on that)
ITO -
     More Difficult than Initially Thought
          Color
          Need to stabilize a-Si input!
```





Task I: Closed Loop Thickness Control I

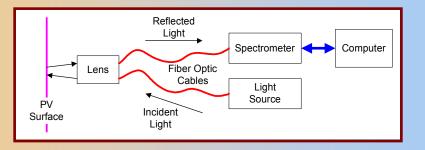
Overview

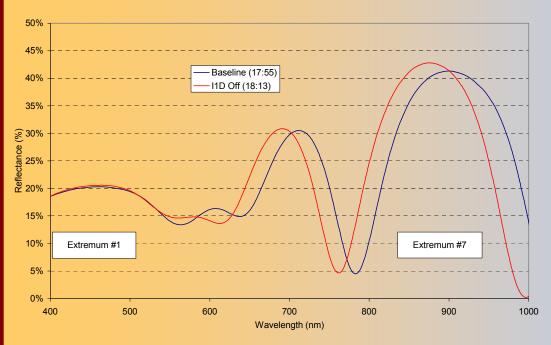










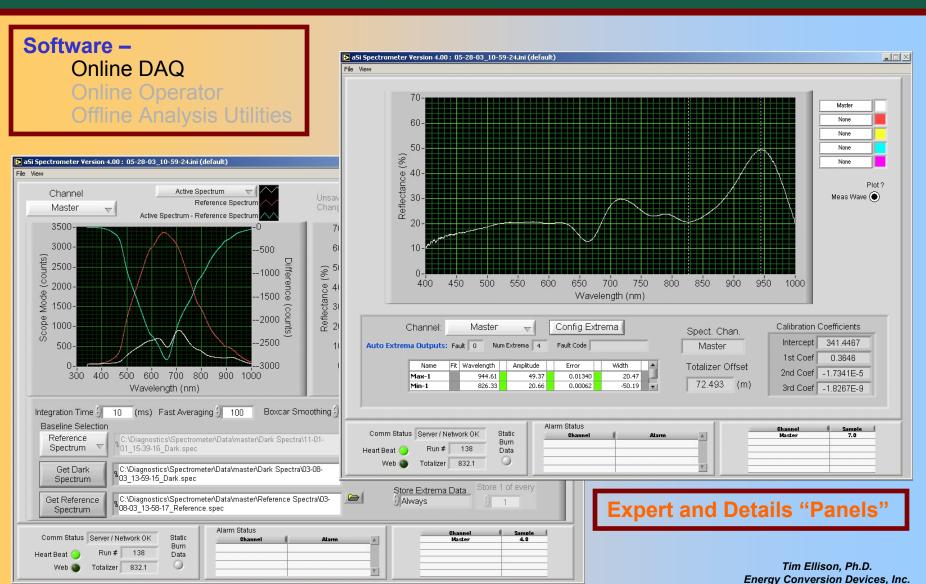








Task I: Closed Loop Thickness Control I



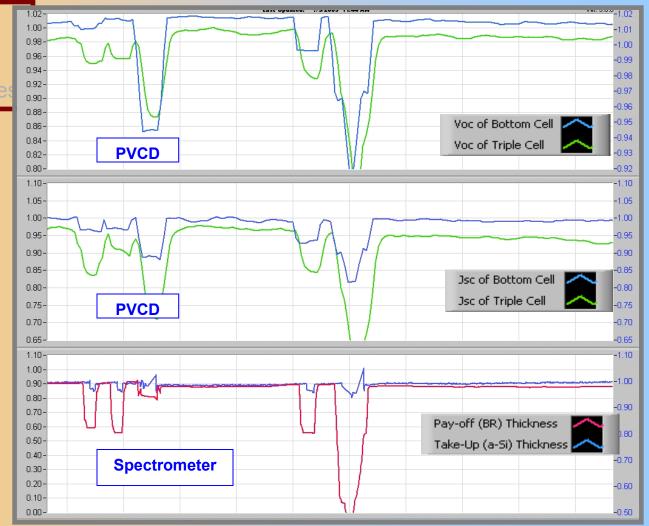


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Task I: Closed Loop Thickness Control I







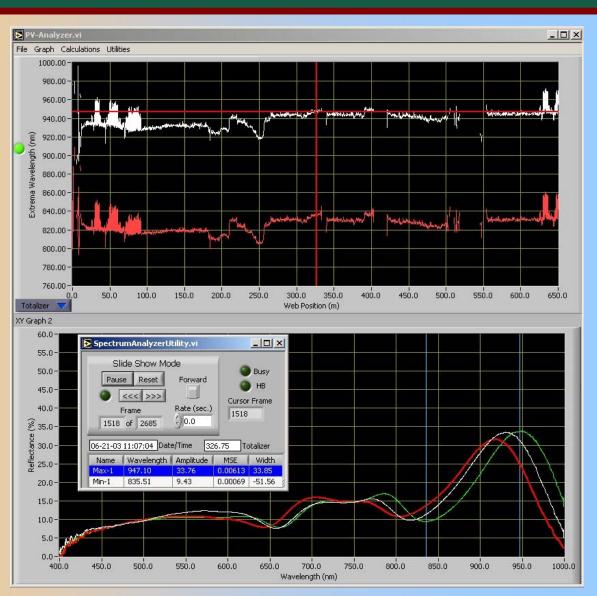
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Software –
Online DAQ
Online Operator
Offline Analysis Utilities

Raw Data (Spectra) are saved and archived so that old "Runs" can be played back to optimize fitting algorithms

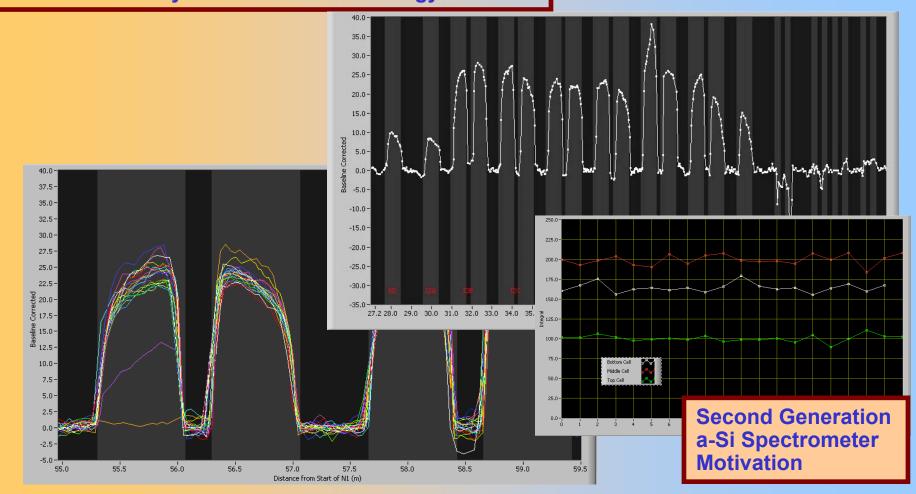








"1-min On-the-Fly Static Burn" Technology – Bonus!



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Task I: Closed Loop Thickness Control I



Second Generation a-Si Spectrometer

Design (really second design – Needed the "A" Team)



- •300 °C Temperatures
- Thermal Cycling
- UHV Compatible
- Avoid a-Si deposition on spectrometer optics
- Moving web must be free from vibration or angular changes
- Located inside a long narrow region between webs
- ·Hidden from visual inspection, hands-on adjustment

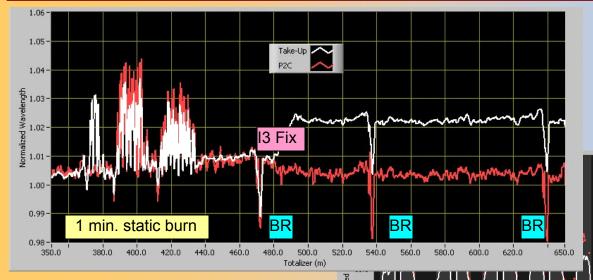




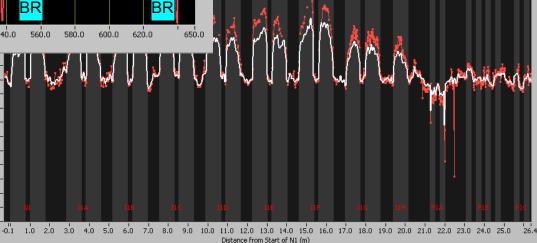




Second Generation a-Si Spectrometer First Operation



-10.0 -15.0 -20.0 --25.0 --30.0 = -35.0 = -40.0 -



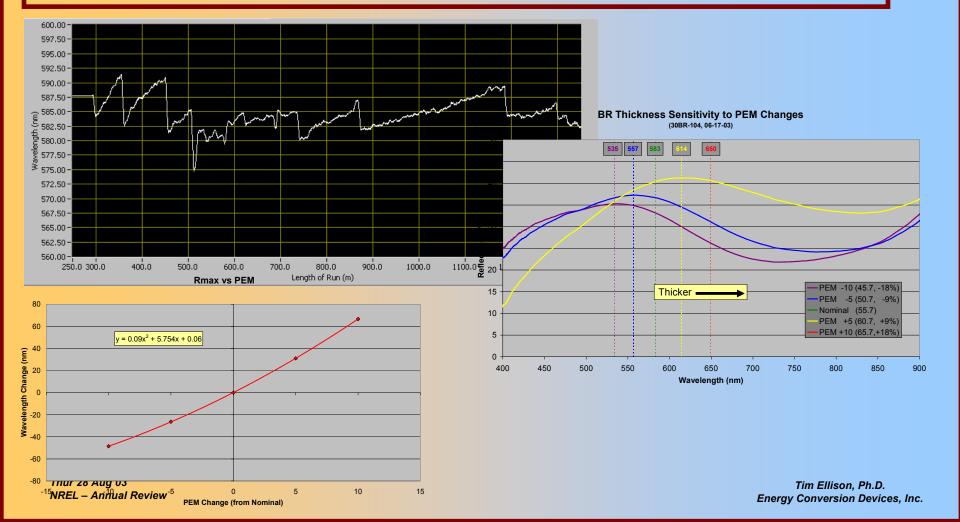




Task I: Closed Loop Thickness Control I

Closed Loop Thickness Control System (BR) (ITO is a can of worms!)

Presently humans close the loop —



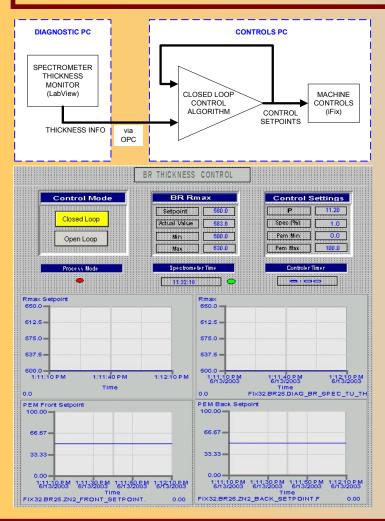


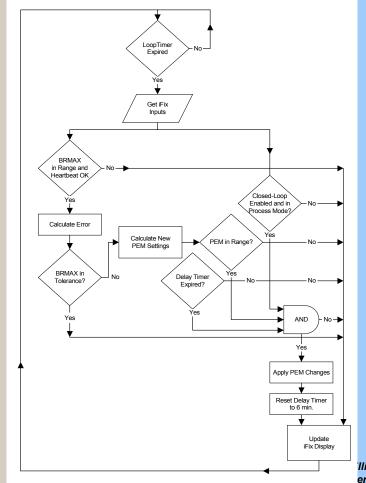




Closed Loop Thickness Control System (BR) (ITO is a can of worms!)

System Design – "Conceptually Simple" – the exceptions are what will get us





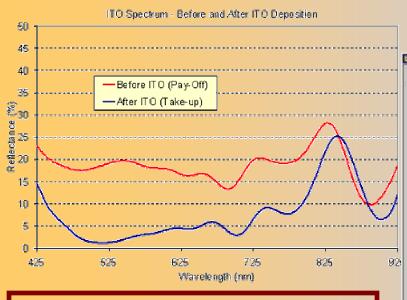
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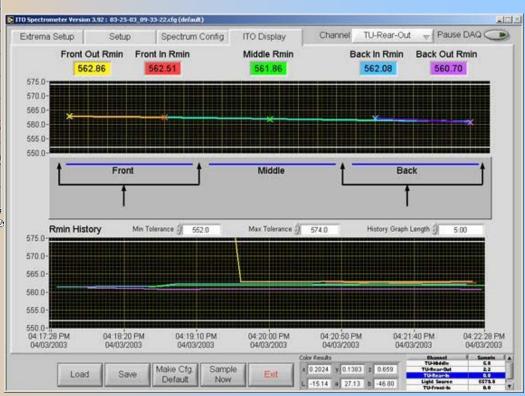


Task I: Closed Loop Thickness Control I

Closed Loop Thickness Control System ITO not conceptually simple --



Color more important than thickness

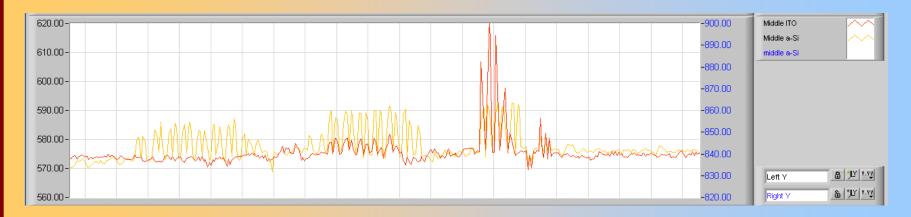








Closed Loop Thickness Control System ITO not conceptually simple --



Top Layer a-Si thickness affects reflection spectrum, and consequently color Best way to control output is to control input

While we had initially thought controlling a-Si thicknesses was beyond the scope of this program, we are now more highly motivated

Will try, initially manually, closing the loop on a-Si top cell thickness before closing the loop on ITO thickness (color).









TASK 2: PV Capacitive Diagnostic Design and Fabrication for Bottom and Middle Cells

- Tim Ellison, Rob Kopf and Wayne Messing (ECD); Dave Dodge (Focus Software)

Milestones

Complete m-1.0.2 Complete initial bench testing of component cell PVCD.

Complete m-1.0.3 Complete bench testing of component high intensity LED light source and light source power supply.

Complete m-1.1.2 Complete preliminary testing of component cell PVCD in production machine.

Complete m-1.3.2 Complete installation of retrofitted component cell PV Capacitive Diagnostic in production equipment.

Complete m-1.4.2 Complete the Phase I portion of the effort under Task 2.

Deliverables

Complete D-1.0.1	Report summarizing bench testing of high intensity LED light source and
	light source power supply
Commission D 4 4 4	Depart supposed in a decision and installation of seven energy call DV

Report summarizing design and installation Complete D-1.1.1 component Capacitive Diagnostic in production equipment.



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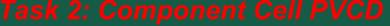


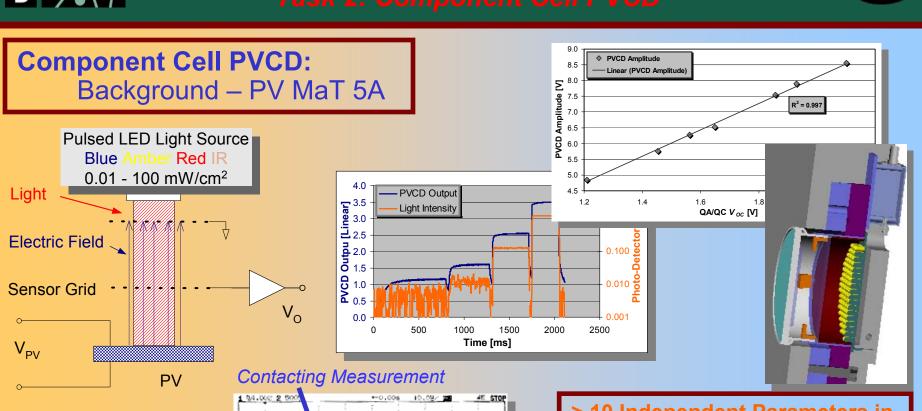
Task 2: Component Cell PVCD

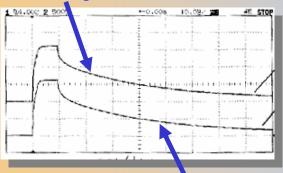
Component Cell PVCD: Design, Fabrication, Testing, Installation, Optimization Background – PV MaT 5A Development **Motivation** Design Challenges Shutter System **Design Summary Light Source** Installation (x3) **Optimization** First Operation/Noise Plasma Noise Killer Summary











> 10 Independent Parameters in **PVCD Waveform – 2 trivial** and well established:

Amplitude: V_{OC}

Initial Derivative: J_{SC}/C

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Tim Ellison, Ph.D. Energy Conversion Devices, Inc.



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Motivation –

Unambiguous V_{oc} , J_{sc}/C , and ? measurements for each component cell

- Pinpoint Problems especially when combined with other diagnostics data (e.g. spectrometers)
- Significant Step Forward Data not available till now, even in offline testing Together with Spectrometers, this system will allow us to embark on a serious program of Continuous Online Optimization – the ultimate goal of this work



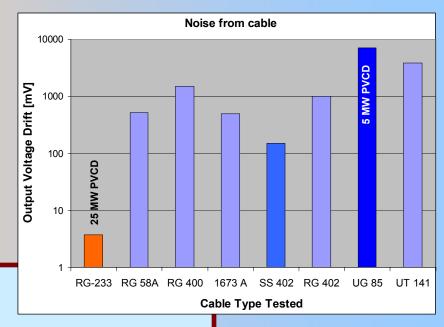
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<u>Design</u>

Challenges
Shutter System
Design Summary
Light Source



Challenges

Go from a few feet to a few inches --

(Discharge Heater, Pre-cooler, Pusher Plate, PVCD)

No access for calibration, viewing, testing, service

Go from "dirty" to UHV-compatible

(Electronics, cables, ...)

Temperature Stabilization (0.1 °C)

Sensor-to-web position stabilization (0.001" for 0.25%)

EMI –

(rf, plasma, heaters, ionized gas ...)

Long cables

Accomplished with Shutter

Measure "web offset voltage"

Apply calibration signals

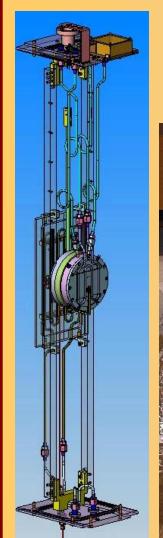
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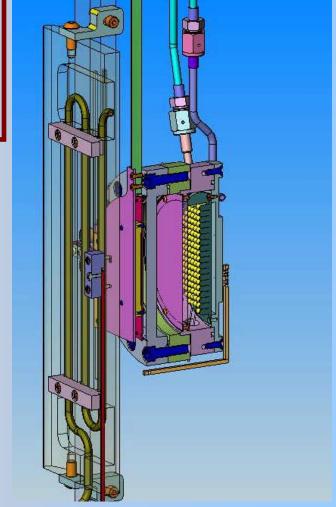




<u>Design</u> Cha

Challenges
Shutter System

Design Summary Light Source



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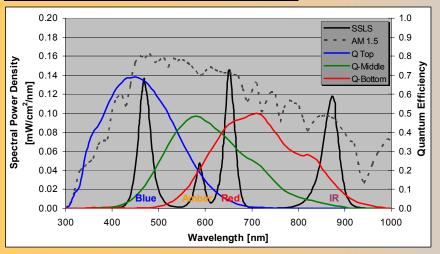




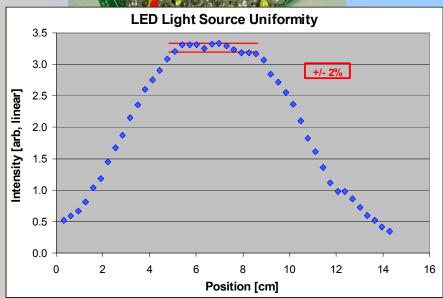
<u>Design</u>

Challenges
Shutter System
Design Summary
Light Source

LED	Wavelength Absorption				
	[nm]	Тор	Middle	Bottom	
Blue	474	1.00	0.19	0.01	
Amber	588	0.41	1.00	0.42	
Red	652	0.09	0.78	1.00	
IR	860	0.00	0.13	1.00	







Has lead to work on an AM 1.5 Class A+ Simulator







Component Cell PVCD: Installation (x3)

The Old "Ship-in-the-Bottle" Trick Improvements:

Notch I-Beams

More robust feedthroughs and electrical connections





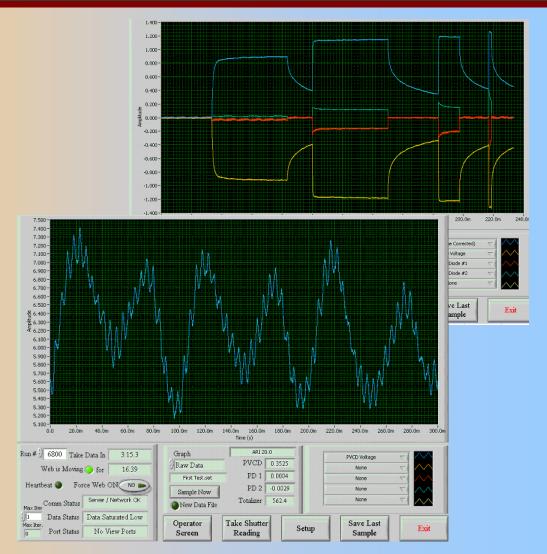


Optimization First Operation/Noise Plasma Noise Killer

Operated splendidly with plasma's and heaters off With system operating, signal-to-

noise ratio (S/N) ≈ 0.5 Was not clear that the system would work

Note – this plasma noise signal may turn out to be a useful diagnostic system -





Comprehensive On-Line Closed-Loop Diagnostic Systems

Task 2: Component Cell PVCD



Optimization

First Operation/Noise

Plasma Noise Killer

Averaging

Line-sinking

"Improbability Filter"

Subtracting initial baseline

Analytical waveform fitting

Post-filtering of waveform parameters

 $S/N \approx 20 (100 X)$

Note: Filtering/Averaging reaches point

of diminishing returns -

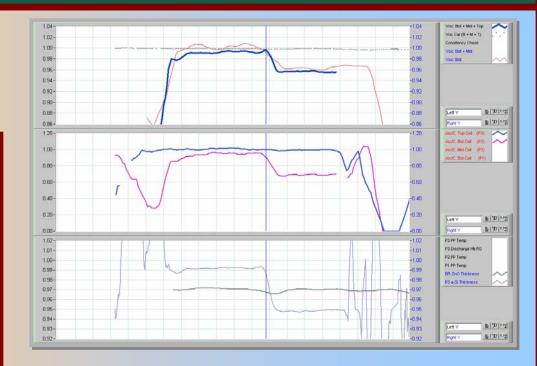
S/N ~ 1/√#samples

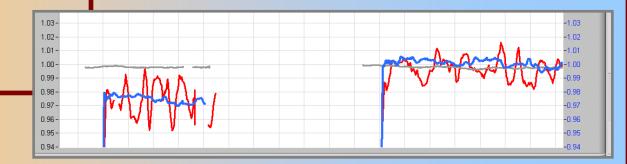
Did provide useful information

But too slow ...

Too noisy for future online

optimization







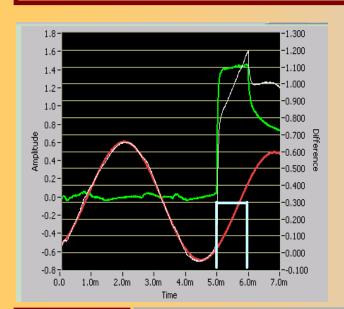
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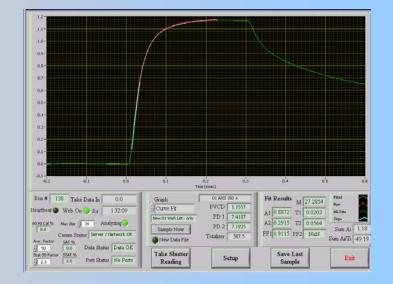
Task 2: Component Cell PVCD

Optimization

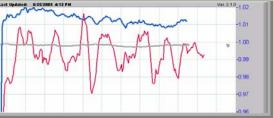
First Operation/Noise Plasma Noise Killer

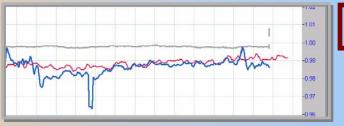


S/N now almost 1000
Perhaps better than TU Chamber System



Before





After

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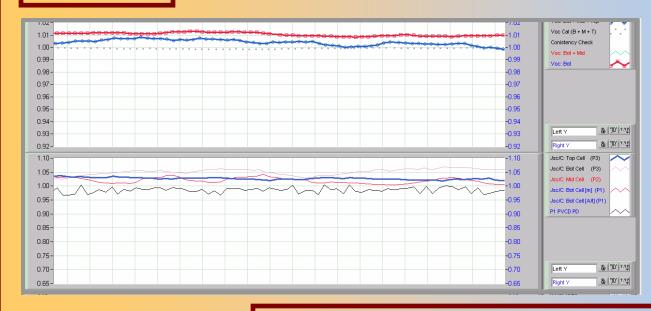
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Task 2: Component Cell PVCD

Summary



S/N been improved by about a factor of 10,000 Still Tweaking

All work can be applied to next generation system for the [Bottom+Middle] PVCD

Clear mechanical improvements identified

S/N and stability appear adequate for envisioned program of Continuous Online Optimization – the ultimate goal









-- Scott Jones, Greg DeMaggio, and Tim Laarman (ECD)

Milestones

Complete	m-1.0.3	Initial	installation	of	plasma	monitoring	sensors	in	pilot	deposition
		machine.								

Complete m-1.1.3. Complete installation of plasma monitoring sensors in pilot deposition machine.

Complete m-1.2.2 Initial characterization of plasmas created at 1 Å/s in pilot deposition machine.

~ 1 month m-1.4.3 Complete characterization of plasmas created at 1 \(\text{A/sec} \) in pilot chamber.

~ 1 month m-1.4.4 Complete the Phase I portion of the effort under Task 3.

Deliverables

~ 1 month D-1.4.1 Summary report of characterization studies of plasmas at 1 A/sec in pilot deposition machine



Comprehensive On-Line Closed-Loop Diagnostic Systems



Task 3: Plasma Diagnostics

<u> Diagnostic Systems –</u>

Plasma Emission Spectrometer –

Hardware

Can we discern differences between plasma characteristics at low and high deposition rates?

In intrinsic-type deposition conditions?

In p-type deposition conditions?

Particle (powder) Detection -

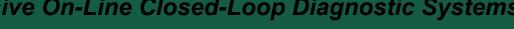
Powder is BAD -

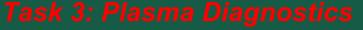
Reduces deposition rates

Can lead to shunts in final product

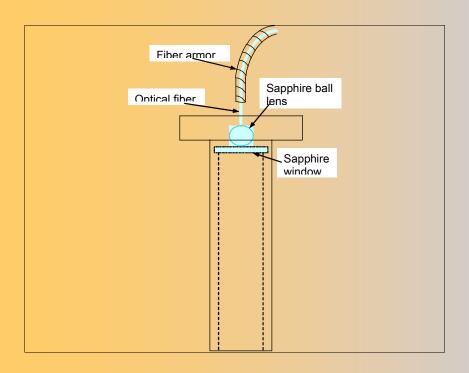
Would any of these techniques be applicable to operations?











Design Challenges

High Temperatures **Deposition onto Optics UHV-Compatible**

Ocean Optics 2000 USB Spectrometer

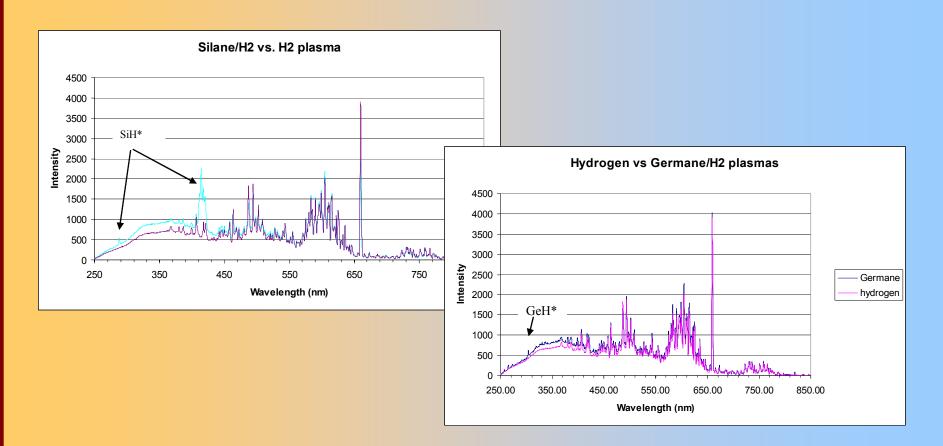




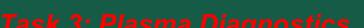
Task 3: Plasma Diagnostics

Plasma Emission Spectrometer – Intrinsic-type deposition conditions

Have Looked at Si:H and Ge:H plasmas

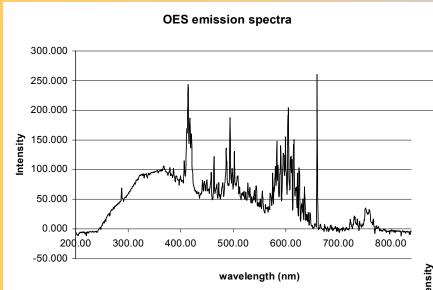








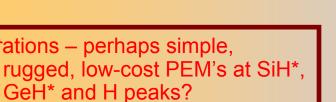
Plasma Emission Spectrometer – Intrinsic-type deposition conditions

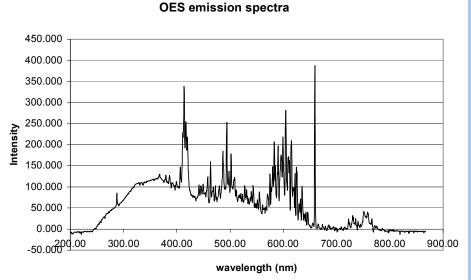


Operations – perhaps simple,

GeH* and H peaks?

Low (1 Å/s) and High (3 Å/s) H₂ **Dilution and Deposition Rates**

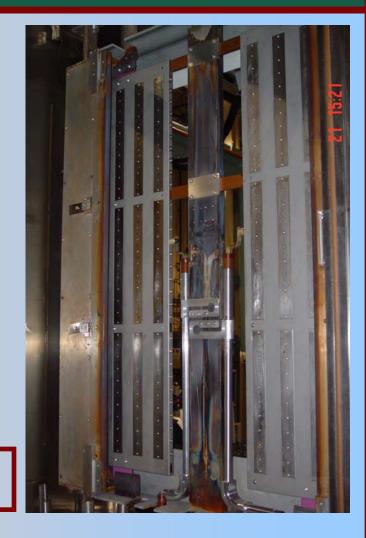






Plasma Emission Spectrometer – p-type deposition conditions

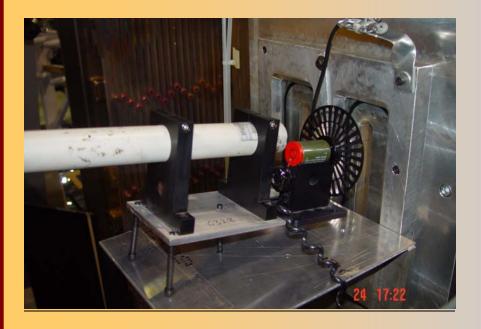
> p-type deposition hardware currently being installed







Laser Particle Detection Hardware



Have observed small response when operating with excessive powder formation conditions







Task 4: Yield Improvements: Substrate Cleaning

Greg DeMaggio (ECD), Gary Di Dio, Peter Nam, Wai Kei Chan (United Solar)

Milestones

Complete	m-1.0.4	Complete setup of OSEE Surface Quality Monitor on United Solar wash
		line.
Complete	m-1.1.4	Complete initial baseline characterization of surface monitor. Correlation

with substrate cleaning parameters.

Complete m-1.2.3 Complete initial investigation of plasma cleaning parameters and correlation with QA/QC data.

~ month m-1.4.5 Complete evaluation of effectiveness of plasma cleaning vs. chemical cleaning.

In Progress m-1.4.6 Complete evaluation of on-line techniques for measuring substrate cleanliness.

m-1.4.7 Complete the Phase I portion of the effort under Task 4.

Deliverables

Complete	D-1.0.2	Report describing surface quality monitor on substrate wash line.				
~ month	D-1.4.2	Report summarizing of plasma vs. chemical cleaning, and correlation with offline QA/QC				
~ monty	D-1.4.3	Report summarizing data from cleanliness monitoring and correlation with offline QA/QC				



ECD and United Solar PV Manufacturing R&D Program

Comprehensive On-Line Closed-Loop Diagnostic Systems





Diagnostics to Monitor Surface Cleanliness in Washing Machine

Installation of Diagnostics

Measurements

Different Substrates

With Varying Wash Conditions

Initial Testing

Matrix Testing

Plasma Cleaning

Initial Measurements

Measurements in Progress

Success in proving Plasma Cleaning works better than Wet Chemical Cleaning would allow us to eliminate one of 4 roll-to-roll Front End Processors – this is our ultimate goal.



Tack A: Viold Improvements: Substrate Cleaning



Diagnostics to Monitor Surface Cleanliness in Washing Machine Installation of Diagnostics



OSEE – Optically Stimulated Electron Emission Instrument-Substrate distance critical A couple iterations on mounting

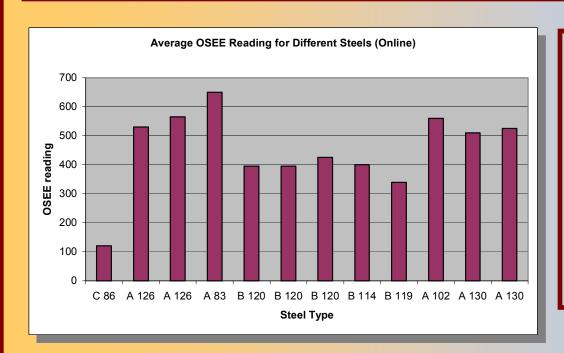




Task 4: Vield Improvements: Substrate Cleaning



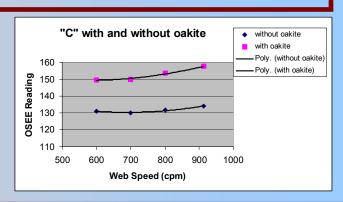
Diagnostics to Monitor Surface Cleanliness in Washing Machine Initial Tests



OSEE signal found to vary significantly with different substrates – we found a correlation with surface finish – the higher the quality of the finish, the higher the OSEE signal.

Absolute surface contamination measurements not possible.

Also found correlations with web speed – system may still provide relative measurements to assess cleaning conditions.



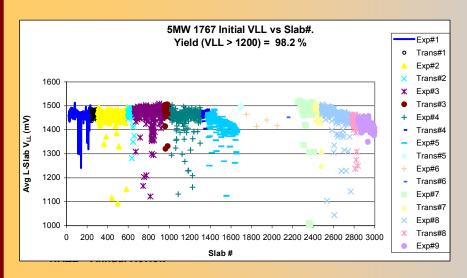


Task 4: Yield Improvements: Substrate Cleaning



Diagnostics to Monitor Surface Cleanliness in Washing Machine Experimental Matrix Relative Measurements

Test #	PH	Speed OSEE reading		Difference	
			PO	TU	
1	pH 8.5	600cm/min	352.7	434.8	23.3%
2		750cm/min	368.7	441.2	19.7%
3		914cm/min	370.0	433.9	17.3%
4	pH 10	600cm/min	375.5	488.3	30.0%
5		750cm/min	384.3	475.9	23.8%
6		914cm/min	391.1	475.0	21.5%
7	pH 12.3	600cm/min	397.7	665.5	67.4%
8		750cm/min	399.4	630.6	57.9%
9		914cm/min	407.1	609.2	49.6%



Results -

Increased Detergent Level (pH) increases OSEE signal –

However, no indication that OSEE signal correlates with degree of shunts in final product.

Test#	PH	Speed	OSEE reading		Difference	Average
			PO	TU	OSEE	V_{LL}
1	6.22	914cm/min	332.00	355.00	23.00	1.48
4	7.50	914cm/min	327.00	337.00	10.00	1.45
2	11.38	914cm/min	329.00	454.00	125.00	1.52
3	11.94	914cm/min	327.00	498.00	171.00	1.49

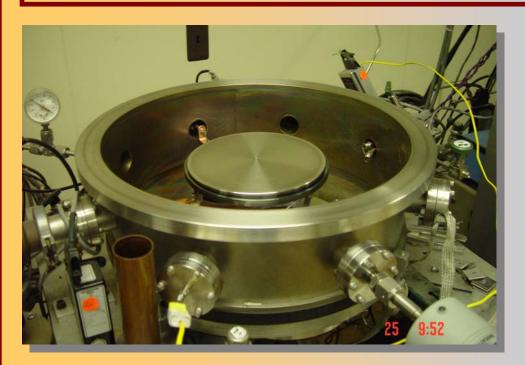
Tim Ellison, Ph.D. Energy Conversion Devices, Inc.







Plasma Cleaning --



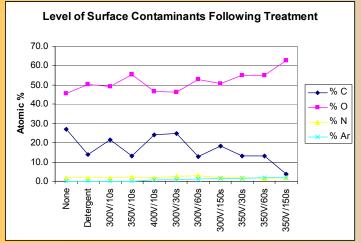
Need to test offline before testing in production machines

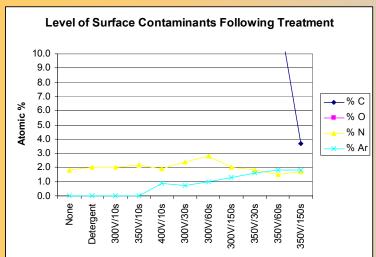


Task 4: Yield Improvements: Substrate Cleaning

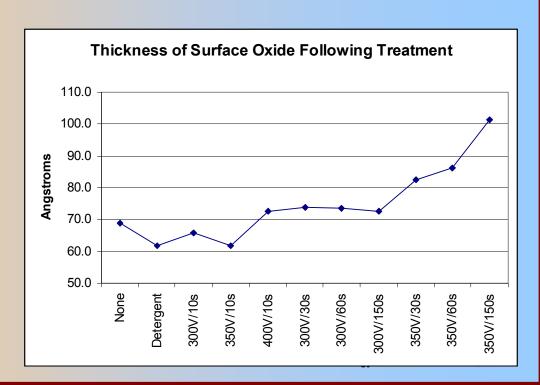


Plasma Cleaning --





Comparisons between chemicallycleaned and plasma-cleaned substrates







Task 4: Yield Improvements: Substrate Cleaning

Plasma Cleaning --

In Progress -

Definitive Test –
Apply oil to surface of substrates
Clean in Production WM and with Plasma Cleaner,
varying conditions

Does plasma cleaning provide same degree of oil cleanup as does chemical cleaning?

Can we then demonstrate cleaning this oil residue in the production BR machine

Then – trial test of substrate using plasma cleaning in BR machine w/o chemical cleaning





Conclusions

We are grateful for NREL's support.

Exponential growth

– it's an interesting thing --

To see a World in a Grain of Sand And a Heaven in a Wild Flower Hold Infinity in the palm of your hand And Eternity in an hour

William Blake, Augeries of Innocence

